

**AMENDMENTS TO THE CLAIMS**

1. **(Currently Amended)** A bipolar electrostatic chuck comprising a first electrode and a second electrode in an interior of an insulating material, ~~said first electrode and second electrode being applied voltages that are different from each other, generates~~ the first electrode and the second electrode being applied voltages between said first electrode and second electrode, so as to generate at least an attracting performance by a gradient force, and attracts a sample by allowing a surface of the insulating material to function as a sample attracting plane, wherein

the insulating material comprises an upper insulating layer, the first electrode, an inter-electrode insulating layer, the second electrode, and a lower insulating layer which are laminated in the order of distance from the sample attracting plane,

the first electrode is formed in a comb-like configuration, and

when the insulating material is viewed from a side cross-sectional view, the first electrode has a plurality of gaps, and the second electrode has a plurality of areas that are not overlapped with the first electrode.

2-3. (Cancelled)

4. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, wherein

~~the first electrode is formed in a comb-like configuration,~~

the second electrode is formed in a comb-like configuration,

the comb-like configuration of the first and second electrodes are alternately arranged,  
and

the second electrode is not overlapped with the first electrode in a normal line direction  
of the sample attracting plane.

5. (Cancelled)

6. (Currently Amended) The bipolar electrostatic chuck according to claim 1, wherein  
~~the first electrode is formed in a comb-like configuration,~~  
the second electrode is formed in a plane having a given planar area, and  
a part of the second electrode is overlapped with the first electrode in a normal line  
direction of the sample attracting plane.

7. (Currently Amended) A ~~The bipolar electrostatic chuck according to claim 1,~~  
~~wherein comprising a first electrode and a second electrode in an interior of an insulating~~  
~~material, the first electrode and the second electrode being applied voltages between said first~~  
~~electrode and second electrode, so as to generate at least an attracting performance by a gradient~~  
~~force, and attracts a sample by allowing a surface of the insulating material to function as a~~  
~~sample attracting plane, wherein~~

the insulating material comprises an upper insulating layer, the first electrode, an inter-  
electrode insulating layer, the second electrode, and a lower insulating layer which are laminated  
in the order of distance from the sample attracting plane,

the first electrode is formed in a lattice-like configuration,

the second electrode is formed in a plane having a given planar area, and

~~a part of the second electrode is overlapped with the first electrode in a normal line direction of the sample attracting plane~~

when the insulating material is viewed from a side cross-sectional view, the first electrode has a plurality of gaps, and the second electrode has a plurality of areas that are not overlapped with the first electrode.

8. (Currently Amended) A The bipolar electrostatic chuck according to claim 1,  
wherein comprising a first electrode and a second electrode in an interior of an insulating  
material, the first electrode and the second electrode being applied voltages between said first  
electrode and second electrode, so as to generate at least an attracting performance by a gradient  
force, and attracts a sample by allowing a surface of the insulating material to function as a  
sample attracting plane, wherein

the insulating material comprises an upper insulating layer, the first electrode, an inter-  
electrode insulating laver, the second electrode, and a lower insulating layer which are laminated  
in the order of distance from the sample attracting plane,

the first electrode is formed in a mesh configuration having a plurality of openings each within a given area,

the second electrode is formed in a plane having a given planar area, and

~~a part of the second electrode is overlapped with the first electrode in a normal line direction of the sample attracting plane~~

when the insulating material is viewed from a side cross-sectional view, the first electrode has a plurality of gaps, and the second electrode has a plurality of areas that are not overlapped with the first electrode.

9-12. (Cancelled)

13. (Currently Amended) The bipolar electrostatic chuck according to claim 1, 7 or 8, wherein a distance between the first electrode and the second electrode is equal to or more than 1  $\mu\text{m}$  and equal to or less than 1000  $\mu\text{m}$ .

14. (Currently Amended) The bipolar electrostatic chuck according to claim 1, wherein ~~the first electrode is formed in a comb-like configuration, and~~  
~~in the case where~~ a electrode width (z) of the first electrode and an inter-electrode gap (z) are made equal to each other, (z) is in a range of 0.15 to 0.5 mm.

15. (Currently Amended) The bipolar electrostatic chuck according to claim 1, 7 or 8, wherein the inter-electrode insulating layer is formed of a resin layer made of one or more resins selected from the group consisting of polyimide, polyamide-imide, polyester, polyethylene terephthalate, epoxy, and acryl.

16. (Currently Amended) The bipolar electrostatic chuck according to claim 1 ~~+~~ 15, wherein the resin layer is formed of one or more resin films.

17. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, 7 or 8, wherein the inter-electrode insulating layer is formed of a ceramic layer made of one or more elements selected from the group consisting of aluminum oxide, aluminum nitride, silicon carbide, silicon nitride, zirconia, and titania.

18. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, 7 or 8, wherein the inter-electrode insulating layer is formed of one or two elements selected from the group consisting of silicon and silicon dioxide.

19. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, 7 or 8, wherein  
an electrically conductive layer is further formed on the surface of the insulating material,  
and  
the surface of the electrically conductive layer serves as the sample attracting plane.

20-21. **(Cancelled)**

22. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, 7 or 8, wherein the inter-electrode insulating layer has a thickness of 1 to 1000  $\mu\text{m}$ .

23. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, 7 or 8, wherein the upper insulating layer has a thickness of 10 to 200  $\mu\text{m}$ .

24. **(Canceled)**

25. **(Currently Amended)** The bipolar electrostatic chuck according to claim ~~1~~ 8, wherein

~~the first electrode is formed in the mesh configuration, and~~ a size of each of the openings is in a range of 0.1 to 3.0 mm.

26-27. **(Canceled)**

28. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, ~~26 or 27~~ 7 or 8, wherein said bipolar electrostatic chuck is capable of attracting an insulating substrate.